### Microelectronics Circuit Analysis and Design

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Chapter 1

Semiconductor Materials and Devices

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Chapter 1-1

#### In this chapter, we will:

- ☐ Gain a basic understanding of semiconductor material properties
  - > Two types of charged carriers that exist in a semiconductor
  - > Two mechanisms that generate currents in a semiconductor
- □ Determine the properties of a pn junction
  - ➤ Ideal current-voltage characteristics of a pn junction diode
- Examine dc analysis techniques for diode circuits using various models to describe the nonlinear diode characteristics
- Develop an equivalent circuit for a diode that is used when a small, time-varying signal is applied to a diode circuit

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Chapter 1-2

#### **Intrinsic Semiconductors**

- ☐ Ideally 100% pure material
  - > Elemental semiconductors
    - Silicon (Si)
      - Most common semiconductor used today
    - Germanium (Ge)
      - First semiconductor used in p-n diodes
  - Compound semiconductors
    - Gallium Arsenide (GaAs)

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Chapter 1-3

# Silicon (Si) Covalent bonding of one Si atom with **four** other Si atoms to

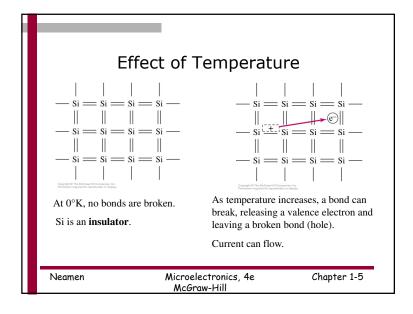
form tetrahedral unit cell.

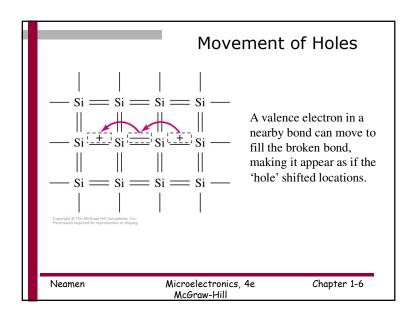
Valence electrons available at edge of crystal to bond to additional Si atoms.

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Chapter 1-4







$$n_i = BT^{3/2}e^{\frac{-E_g}{2kT}}$$

B - coefficient related to specific semiconductor

T - temperature in Kelvin

E<sub>o</sub> – semiconductor bandgap energy

k – Boltzmann's constant

$$n_i(Si,300K) = 1.5x10^{10} cm^{-3}$$

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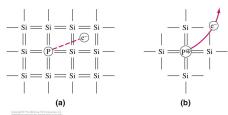
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#### **Extrinsic Semiconductors**

- ☐ Impurity atoms replace some of the atoms in crystal
  - ➤ Column V atoms in Si are called <u>donor impurities</u>.
  - Column III in Si atoms are called <u>acceptor</u> <u>impurities</u>.

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# Phosphorous - Donor Impurity in Si

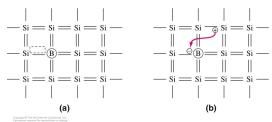


Phosphorous (P) replaces a Si atom and forms four covalent bonds with other Si atoms.

The  $\underline{\text{fifth}}$  outer shell electron of P is easily **freed** to become a conduction band electron, adding to the number of electrons available to conduct current.

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# Boron - Acceptor Impurity in Si



Boron (B) replaces a Si atom and forms only **three** covalent bonds with other Si atoms.

The missing covalent bond is a hole, which can begin to move through the crystal when a valence electron from another Si atom is taken to form the fourth B-Si bond.

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#### **Electron and Hole Concentrations**

ni = intrinsic carrier concentration (geo. Mean)

n = electron concentration

p = hole concentration

 $n_i^2 = n \cdot p$ 

n-type:

 $n = N_D$ , the donor concentration

 $p = n_i^2 / N_D$ 

p-type:

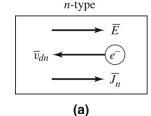
 $p = N_A$ , the acceptor concentration

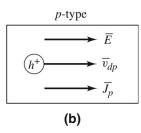
 $n = n_i^2 / N_A$ 

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#### **Drift Currents**



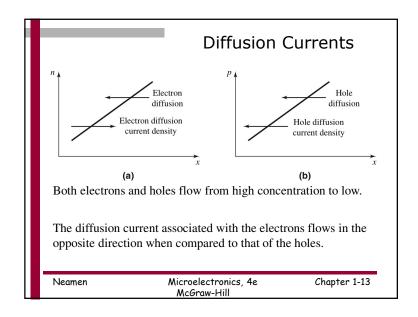


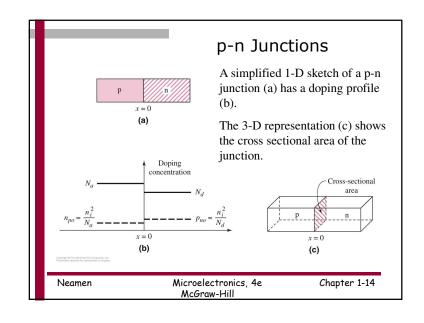
Electrons and hole flow in opposite directions when under the <u>influence of an electric field</u> at different velocities.

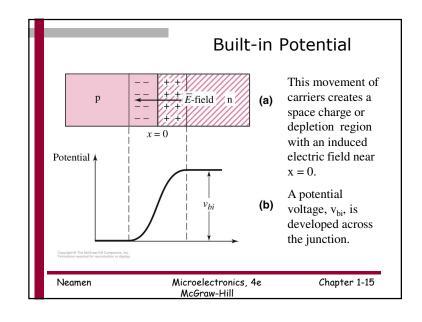
The drift currents associated with the electrons and holes are in the same direction.

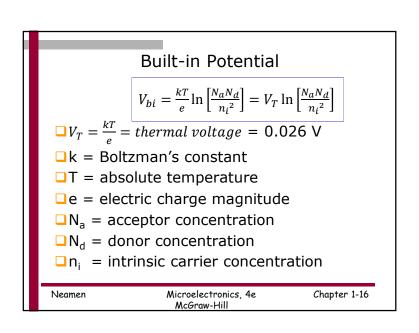
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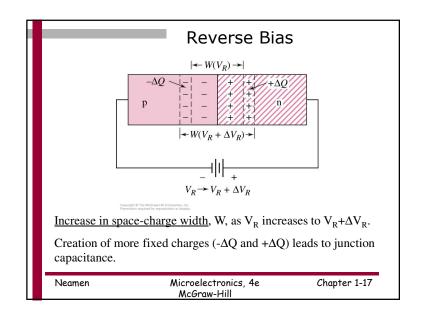
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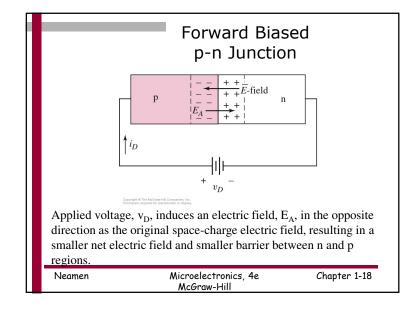


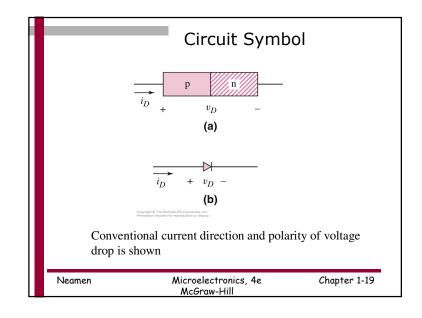


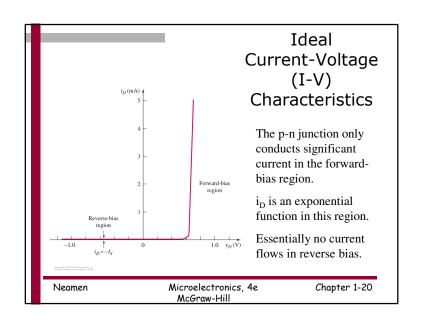












# **Ideal Diode Equation**

A fit to the I-V characteristics of a diode yields the following equation, known as the ideal diode equation:

$$I_D = I_s (e^{\frac{qv_D}{kT}} - 1)$$

kT/q is also known as the thermal voltage, V<sub>T</sub>.

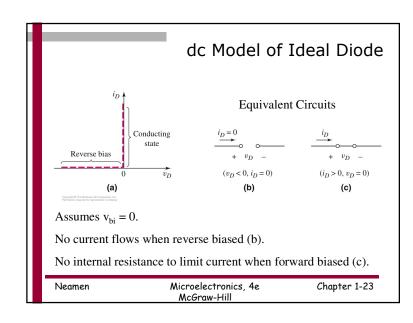
 $V_T = 25.9 \text{ mV}$  when T = 300 K, room temperature.

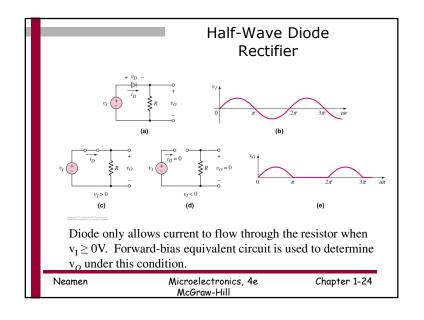
$$I_D = I_s(e^{\frac{v_D}{V_T}} - 1)$$

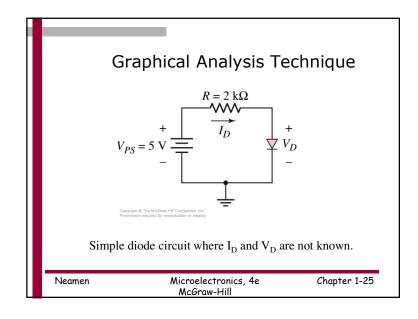
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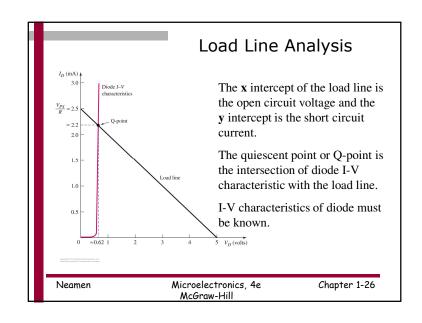
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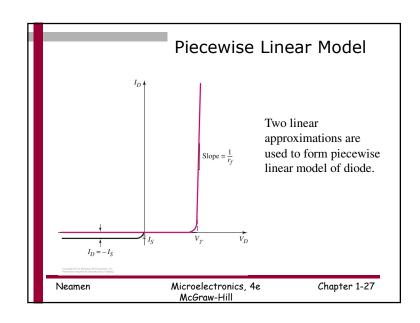
#### Breakdown Voltage The magnitude of the breakdown voltage (BV) is smaller for heavily doped diodes as $BV_1$ compared to more lightly doped diodes. doped Current through a diode increases rapidly once High doped breakdown has occurred. Neamen Microelectronics, 4e Chapter 1-22 McGraw-Hill

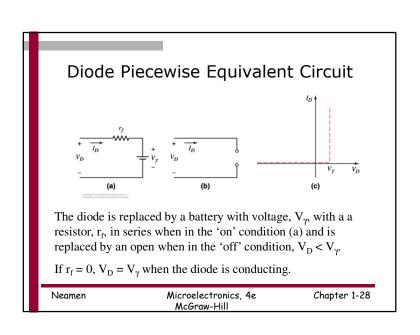


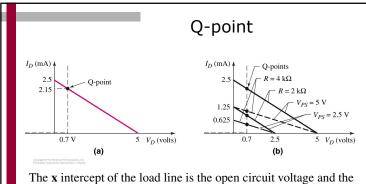












y intercept is the short circuit current.

The Q-point is dependent on the power supply voltage and the resistance of the rest of the circuit as well as on the diode I-V characteristics.

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Chapter 1-29

# ac Circuit Analysis Combination of dc and sinusoidal input voltages modulate the operation of the diode about the Q-point. Neamen Microelectronics, 4e Chapter 1-30 McGraw-Hill

# ac Circuit Analysis

$$\begin{split} v_D &= V_D + v_d \\ i_D &= I_s \Big(e^{\frac{v_D}{V_T}} - 1\Big) \cong I_s \Big(e^{\frac{v_D}{V_T}}\Big) = I_s \Big(e^{\frac{V_D}{V_T}}\Big) \ (e^{\frac{v_d}{V_T}}) \end{split}$$

For small signals when  $v_d \ll V_T$   $e^{v_d/V_T} \cong 1 + {^{v_d}/_{V_T}}$ 

$$e^{v_d/V_T} \cong 1 + \frac{v_d}{V_d}/V_T$$

Then 
$$I_s(e^{\frac{V_D}{V_T}})(1 + {^vd}/_{V_T}) = I_D(1 + {^vd}/_{V_T}) = I_{DQ} + i_d$$

$$I_{DQ} \equiv I_s(e^{\frac{V_D}{V_T}})$$
 and  $i_d \equiv (\frac{I_{DQ}}{V_T})v_d$ 

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